

Docket No.: MUH-11987

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : JÖRG HAUSSMANN ET AL.

Filed : Concurrently herewith

Title : POLYBENZOXAZOLE PRECURSORS, PHOTORESIST SOLUTION, POLYBENZOXAZOLE, AND PROCESS FOR PREPARING A POLYBENZOXAZOLE PRECURSOR

J1017 U.S. PTO
10/008796
11/13/01



INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks,
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

German published Non-Prosecuted Patent Application DE 37 16 629 A1 (Ahne et al.), dated December 8, 1988, heat resistant positive resists and method to manufacture heat resistant relief structures;

European Patent Application 0 023 662 A1 (Ahne et al.), dated February 11, 1981, heat resistant positive resists and method to manufacture heat resistant relief structures;

European Patent Application EP 0 905 169 A2 (Sezi et al.), dated March 31, 1999, polybenzoxazole and polybenzothiazole prestages;

European Patent Application EP 0 905 170 A2 (Sezi et al.), dated March 31, 1999, polybenzoxazole and polybenzothiazole prestages;

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications,

patents and/or publications, it is because no existing translation is readily available to the applicant.

Respectfully submitted,


For Applicants

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